

description

The Model 1402 Ion Source features high beam currents at very low beam energies. It also may be operated at high beam energies (up to 3 keV) to provide additional depth profiling and sample cleaning capability. Likely applications would include charge compensation, ion scattering, and studies of ion/solid interactions.

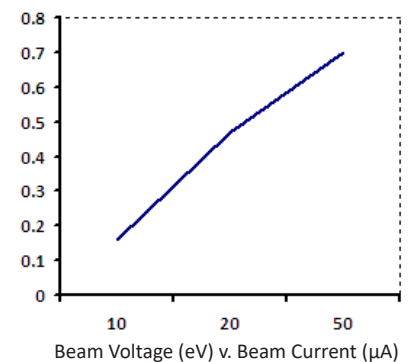
Ion generation is by means of electron impact ionization with dual filaments for long source life without having to break system vacuum. The filaments are located off axis to prevent line of sight deposition of the filament material onto the sample.

benefits

- Unique ion source for stable emission
- Dual Tungsten alloy filaments
- Power supply and deflection supply in a single 5.25"-high 19" rack-mount
- UHV construction
- Electrical connections and gas inlet all rear of housing for simplified installation

specifications

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|------------------|--|
| Beam Energy | 5 eV to 3 keV continuously variable (5 keV optional) |
| Beam Current | 5 μ A maximum @ 2 keV Beam |
| Spot Size (FWHM) | 1.5 mm @ 1.0 μ A, 20 eV 1.0 mm @ 2.0 μ A, 40 eV 0.2 mm @ 3.0 μ A, 1 kV 20 mm Working Distance |
| Electrical | 115/220 V, 50/60 Hz Auto-select |
| Flanges | 2.75 in (70 mm) CF for mounting 1.33 in (34 mm) CFF gas inlet |



All specifications are subject to change without notice.